REMARKS

Claims 2 – 11, 13 – 22, 25, and 28 – 33 are pending. Claims 30 – 32 have been allowed.

Rejection Under 35 U.S.C. § 102

Claims 2 – 6, 8 – 11, 13, 14, 16 – 22, 25, 29 and 33 have been rejected under 35 U.S.C. § 102(b) as being anticipated by EP 380 236 (Leir). The rejection is traversed for the following reasons.

Leir discloses water-dispersible organopolysiloxane polyurea block copolymers comprising the repeating unit of formula I (see, for example, page 3, line 30, through page 4, line 11, of Leir) that are formed by the incorporation of ionic groups along the polymer chain (see, for example, page 6, lines 53 – 54).

Applicants claim priming compositions, pressure sensitive adhesives, and articles comprising a polydiorganosiloxane polyurea copolymer comprising electron rich groups selected from the group consisting of tertiary amine groups, pyridine groups, and combinations thereof (that is, the group consisting of electron rich tertiary amines, electron rich pyridine groups, and electron rich combinations thereof), the priming composition being capable of adhering to a substrate comprising acid functional groups.

The Examiner has asserted that tertiary amines taught in Leir, and any tertiary amines, meet the requirement of electron rich groups. Tertiary amine containing segments of copolymers can, however, be protonated and therefore not meet the requirement of electron rich groups. Leir, for example, teaches block copolymers containing protonated (that is, ionic or ionized tertiary amine, not electron rich tertiary amine) containing segments.

The Examiner has specifically asserted that the tertiary amines taught in Leir in Example 1 at the bottom of page 8 meet the requirement of electron rich groups. In Example 1, Leir appears to use triethylamine to deprotonate an acid group, which is present in the polymer. In particular, it appears that Leir adds triethylamine to deprotonate 2,2-dimethylol propionic acid. 2,2-Dimethylol propionic acid is a diol. It therefore reacts into the polymer, and can then be deprotonated to yield an ionic acid group. The triethylamine in Example 1 is not present in the polymer. It therefore cannot be said that the block copolymers of Leir comprise an electron rich tertiary amine group.

In addition, Leir does not appear to teach or suggest that electron rich groups would provide self-priming capability. Leir therefore does not teach or suggest the claimed invention. Applicants respectfully request that the rejection under § 102 based on Leir be withdrawn.

Rejection Under 35 U.S.C. § 103

Claims 7, 15, and 28 have been rejected under 35 U.S.C. § 103 as being unpatentable over Leir. The rejection is traversed for the following reasons.

As discussed above, Leir does not teach or suggest electron rich groups selected from the group consisting of tertiary amine groups, pyridine groups, and combinations thereof. Leir does not teach or suggest that electron rich groups would provide self-priming capability or that electron rich groups would enable adherence to substrates comprising acid functional groups (that is, substrates comprising groups such as, for example, carboxylic acid, phosphoric acid, or sulfuric acid) such as, for example, poly(ethylene/acrylic acid), poly(ethylene/methacrylic acid), or poly(ethylene/vinyl acetate) substrates. Applicants have discovered that electron rich groups provide self-priming capability, and that there is no need for a secondary primer, particularly when the composition is disposed on a substrate (e.g., backing) containing electron poor groups such as acid-functional groups (see, for example, page 3, line 28, through page 4, line 2).

Applicants have also discovered that the compositions of the invention exhibit surprising shear strength relative to conventional silicone polyurea pressure sensitive adhesive when coated onto substrates comprising acid functional groups (see, for example, page 30 wherein the shear strength of coatings comprising the composition of the invention were 10,000 mins.)

Applicants therefore respectfully request that the rejection under § 103 based upon Leir be withdrawn.

Concluding Remarks

In view of the above, it is submitted that the application is in condition for allowance. Reconsideration and allowance of Applicants' claims are respectfully requested.

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Respectfully submitted,

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